

Abstract of the Disclosure

A composition for forming a coating film, comprising a reaction product of a tantalum alkoxide and at least one
5 compound selected from carbamic acid, carboxylic acid and carboxylic anhydride and a solvent. A tantalum oxide film is obtained by forming a coating film of this composition and thermally and/or optically treating the coating film. This tantalum oxide film has a large dielectric constant and
10 a small leak current.